

Integration of Technology for Enhanced Learning among Generation Y and Z Nursing Students

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Abstract : Generation Y and Z nursing students have a much higher need for technology-based stimulation than previous generations, as they may find traditional methods of education boring and disinterested. These generations prefer experiential learning and the use of advanced technology for enhanced learning. Therefore, nursing educators must acquire knowledge to make better use of technology and technological tools for instruction. Millennials and generation are digital natives, optimistic, assertive, want engagement, instant feedback, and collaborative approach. The integration of technology and the efficacy of its use can be challenging for nursing educators. The SAMR (substitution, augmentation, modification, and redefinition) model designed and developed by Dr. Ruben Puentedura can help nursing educators to engage their students in different levels of technology integration for effective learning. Nursing educators should understand that technology use in the classroom must be purposeful. The influx of technology in nursing education is ever-changing; therefore, nursing educators have to constantly enhance and develop technical skills to keep up with the emerging technology in the schools as well as hospitals. In the Saskatchewan Collaborative Bachelor of Nursing (SCBSCN) program at Saskatchewan polytechnic, we use technology at various levels using the SAMR model in our program, including low and high-fidelity simulation labs. We are also exploring futuristic options of using virtual reality and gaming in our classrooms as an innovative way to motivate, increase critical thinking, create active learning, provide immediate feedback, improve student retention and create collaboration.

Keywords : generations, nursing, SAMR, technology

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